

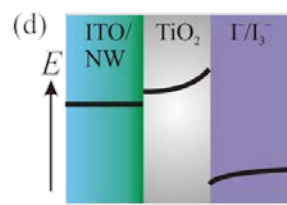
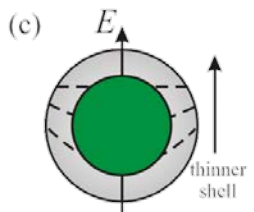
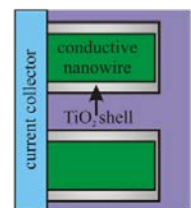
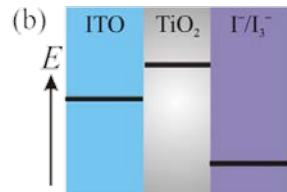
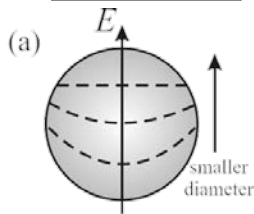
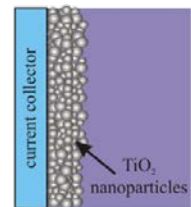
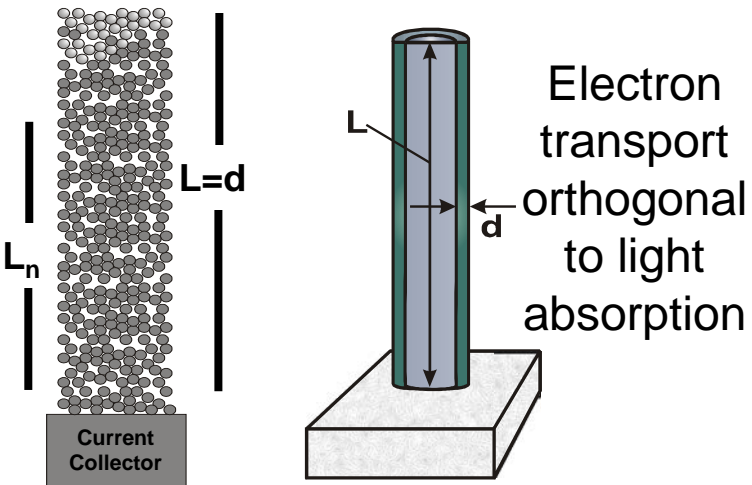
Kirk J. Ziegler

Associate Professor of Chemical Engineering

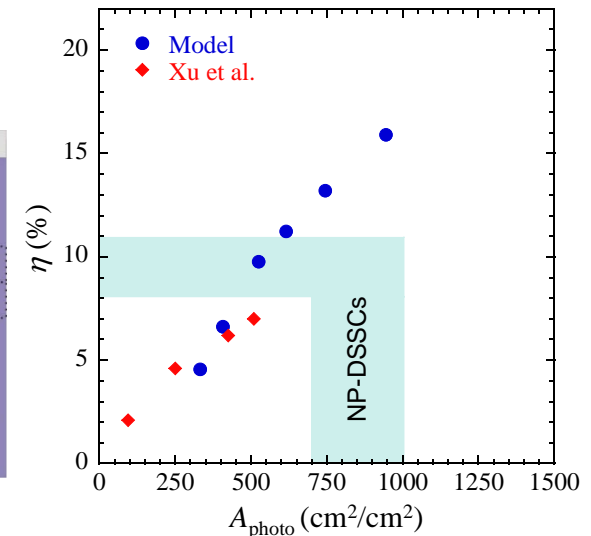
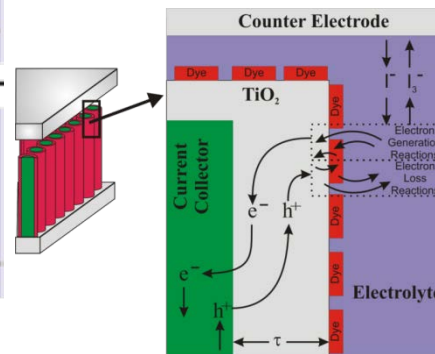
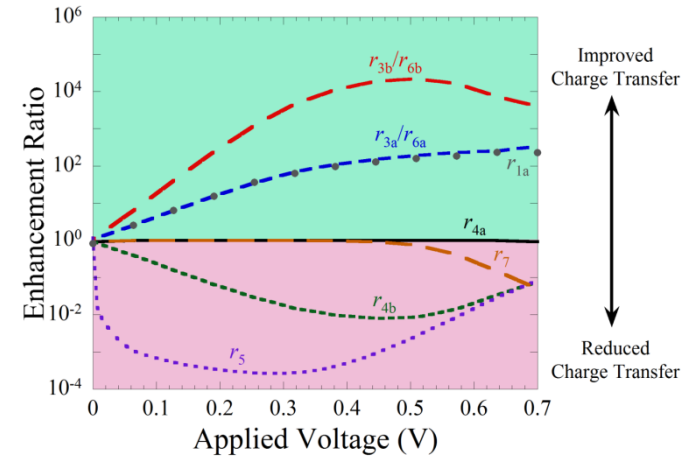
Website: <http://ziegler.che.ufl.edu>



# Nanowire-based dye-sensitized solar cells (DSSCs)



#	Reaction
(1a)	$A \text{ Red} + nh^+ \xrightleftharpoons[k_{b,1a}]{k_{f,1a}} B \text{ Ox} + ne^-$
(2)	$S_g + h\nu \rightarrow S_1^*$
(3a)	$S_1^* \xrightarrow{k_{3a}} S_3^*$
(3b)	$S_3^* \xrightarrow{k_{3b}} S_g$
(4a)	$S_1^* + h^+ \xrightarrow{k_{4a}} S^+ + e^-$
(4b)	$S_3^* + h^+ \xrightarrow{k_{4b}} S^+ + e^-$
(5)	$S^+ + e^- \xrightarrow{k_{5b}} h^+ + S_g$
(6a)	$B \text{ Ox} + nS_1^* \xrightarrow{k_{b,6a}} nS^+ + A \text{ Red}$
(6b)	$B \text{ Ox} + nS_3^* \xrightarrow{k_{b,6b}} nS^+ + A \text{ Red}$
(7)	$A \text{ Red} + nS^+ \xrightarrow{k_{f,7}} B \text{ Ox} + nS_g$



- Better physics
- Lower surface area

- Calculations demonstrate potentially higher efficiencies
- Unique ability to 'tune' some reactions

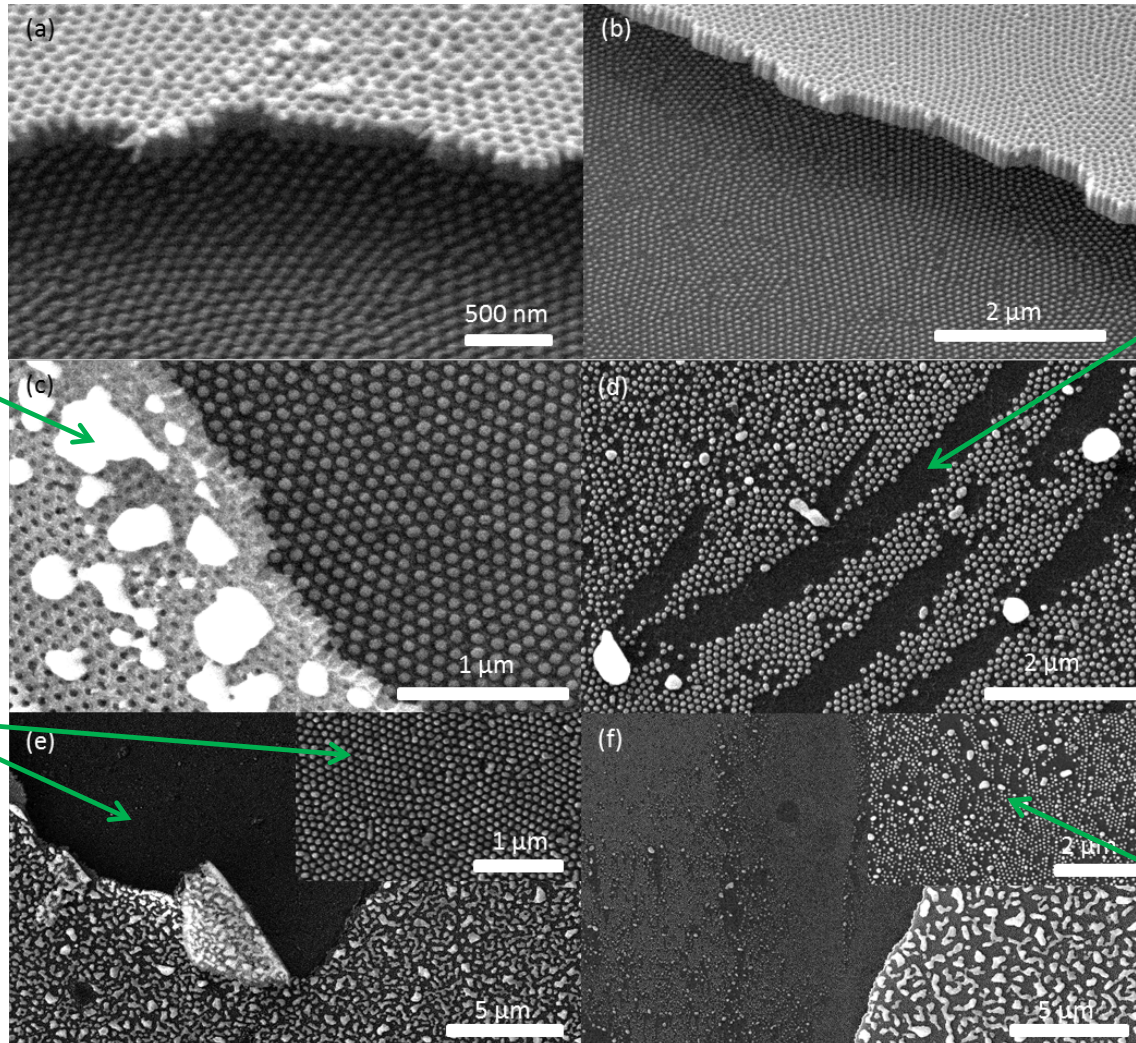


# Thermally-stable nanoparticle arrays

NPs in Si nanocavities

NPs on normal Si surface

No annealing



Template used to generate both nanoparticle arrays

Widespread agglomeration

Ostwald ripening and agglomeration observed on top of AAO template and on normal Si surface

Continued Ostwald ripening and agglomeration

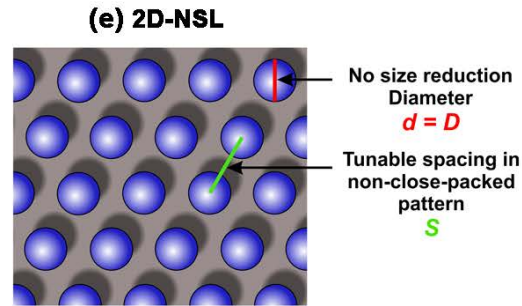
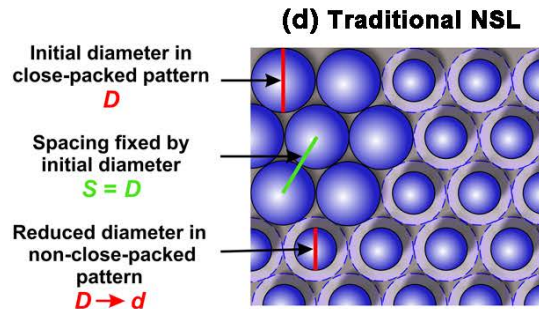
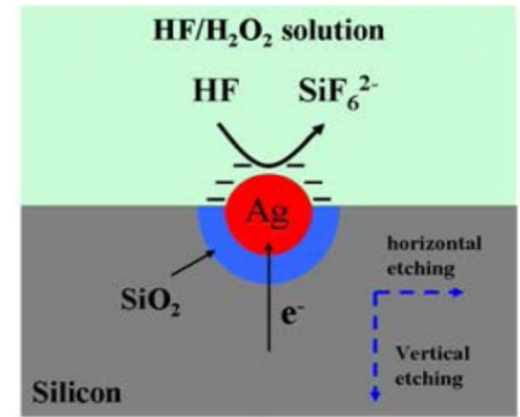
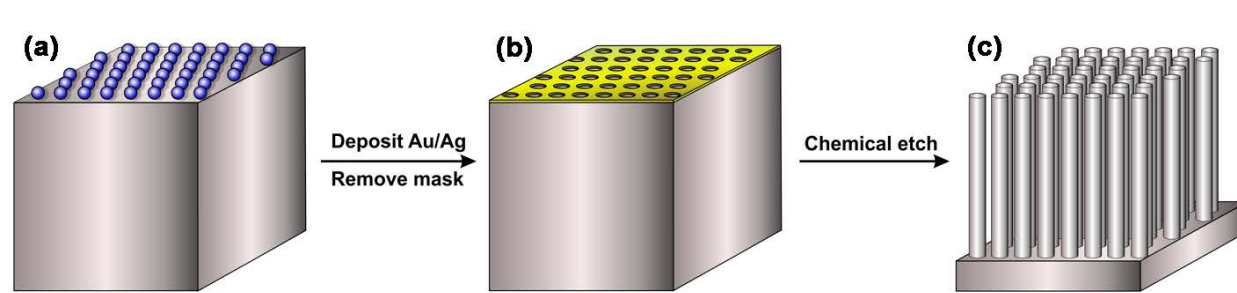
Agglomeration only on template

Annealed at 600 °C for 3 h

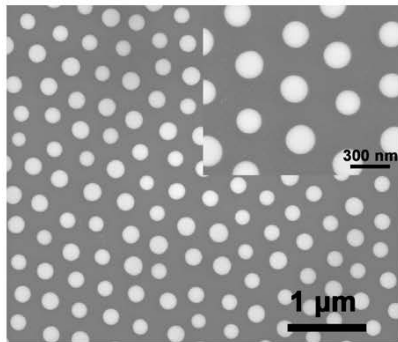
High-res image of nanocavity shows almost no change

Annealed at 600 °C for 11 h

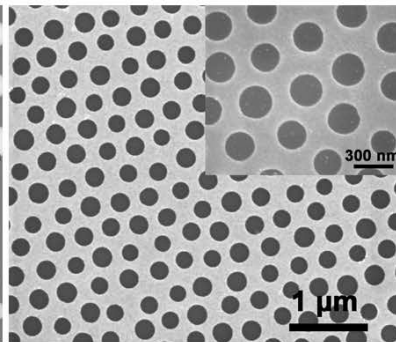
# Controlled fabrication of Si nanowire arrays



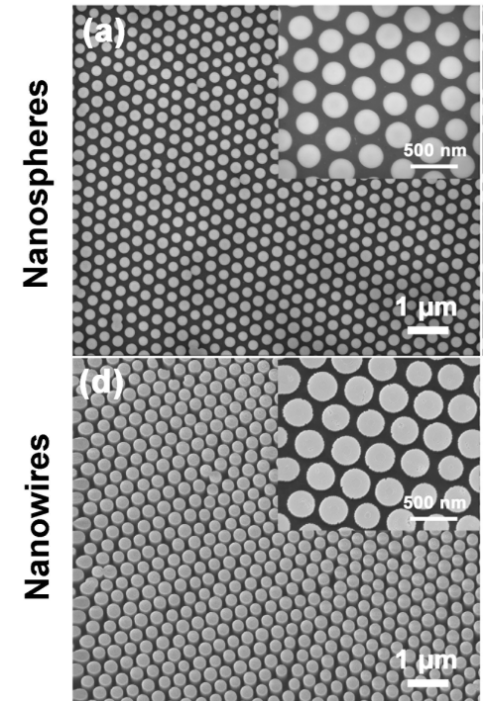
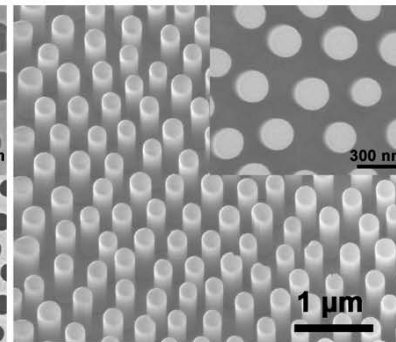
**(f) SiO<sub>2</sub> Nanospheres**



**(g) Au film**

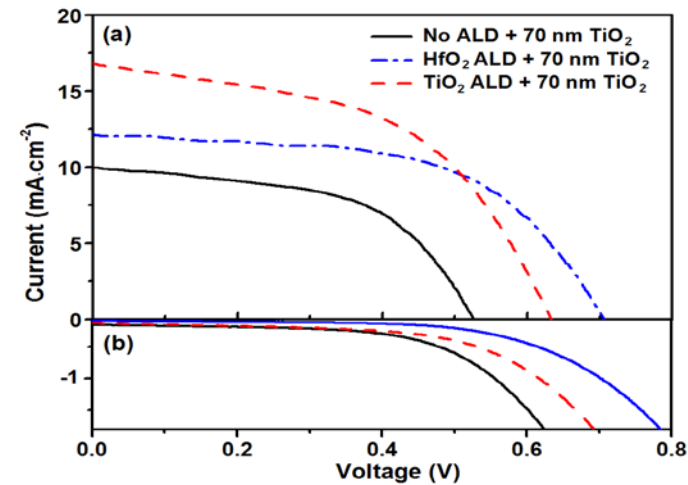
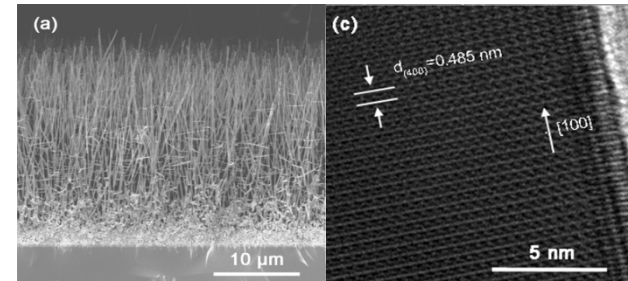
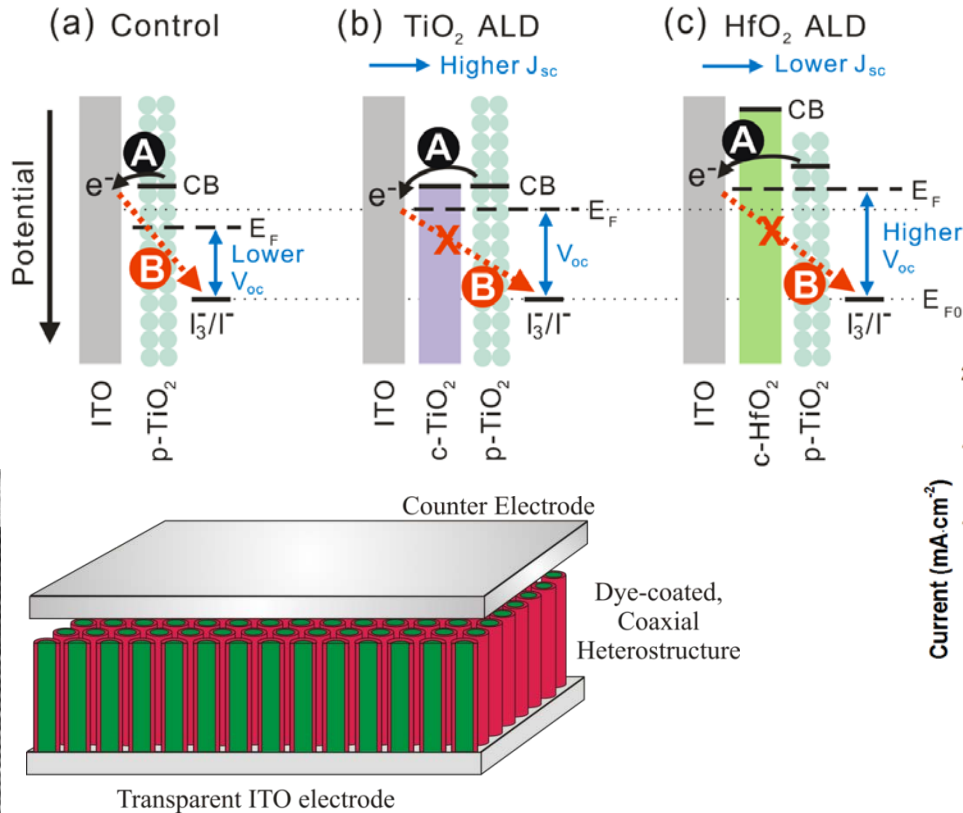


**(h) Si Nanowires**





# NW-based DSSC performance



	V <sub>oc</sub> (V)	J <sub>sc</sub> (mA·cm <sup>-2</sup> )	FF (%)	η (%)	Dye loading (x10 <sup>-8</sup> mol·cm <sup>-2</sup> )
Control	0.52 ± 0.03	9.96 ± 0.07	54.2 ± 0.9	2.82 ± 0.08	1.51
HfO <sub>2</sub> ALD	0.71 ± 0.03	12.17 ± 0.06	55.8 ± 0.6	4.83 ± 0.09	1.61
TiO <sub>2</sub> ALD	0.63 ± 0.04	16.80 ± 0.05	50.7 ± 0.7	5.38 ± 0.05	1.57